



02-18-05

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No.10/666,025
Filing DateSeptember 17, 2003
Inventor..... Cem Basceri et al.
AssigneeMicron Technology, Inc.
Group Art Unit 1762
Examiner Timothy Howard Meeks
Attorney's Docket No. MI22-2407
Title Plasma Enhanced Chemical Vapor Deposition Method of Forming
a Titanium Silicide Comprising Layer

RESPONSE TO NOVEMBER 22, 2004 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Office Action dated November 22, 2004, Applicant
amends and remarks as follows:

AMENDMENTS

02/22/2005 MWOLDGE1 00000024 10666025

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